

Title (en)
Improved plasma spraying

Title (de)
Verbessertes Plasmaspruhen

Title (fr)
Pulvérisation à plasma améliorée

Publication
EP 0887432 A2 19981230 (EN)

Application
EP 98303270 A 19980428

Priority
GB 9712801 A 19970619

Abstract (en)
An apparatus 1 for the plasma spraying of a substrate 2 comprises a reaction chamber 3 at one end of which is located a plasma torch. A plasma forming gas is delivered under pressure to the torch such that a plasma jet is produced which extends along the length of the reaction chamber 3. An inlet port 8 is provided in the torch for the passage therethrough of a powder material and inlet ports 4 are provided in the reaction chamber 3 for injecting a reactive gas such as methane into the plasma jet. <IMAGE>

IPC 1-7
C23C 4/12

IPC 8 full level
C23C 4/12 (2006.01)

CPC (source: EP)
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Cited by
US2013157040A1; CN109847673A; CN114786804A; US6428600B1

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